## 4.2 V Wearable Asymmetric Supercapacitor Devices Based on VO<sub>x</sub>//MnO<sub>x</sub>

# **Electrode and Eco-friendly Deep Eutectic Solvent-Based Gel Electrolyte**

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## Fabrication of nanoporous VO<sub>x</sub>/PGP and MnO<sub>x</sub>/PGP electrodes

The PGP electrode as a cleaned film (area ~6 cm<sup>2</sup>) was pretreated by cleaning in ethanol (2 min), soaking in 0.3M HCl (10 min), rinsing with deionized water, and then drying in a fume cupboard at 27 °C. Metal-nucleation layers were produced on PGP substrates by a Pt sputtered coating of thickness ~100 nm. The Pt/PGP substrates were highly conducting (>1000 S/cm). A nanoporous VO<sub>x</sub> layer was loaded onto the Pt/PGP substrate by electrochemical anodic deposition at 1.2 V in a mixture (volume ratio 1:1) of deionized water

and ethanol containing 0.2 M VOSO<sub>4</sub> and 0.1 M Na(CH<sub>3</sub>COO) to assemble the nanoporous VO<sub>x</sub>/PGP electrodes with a saturated calomel electrode (SCE) and a Pt counter electrode. The Ni-nanotube layer was prepared on a PGP substrate with electrodeposition at 27°C with a SCE and a Pt counter electrode. Firstly, Cu-Ni layers were electrodeposited from a plating solution (0.5 M NiSO<sub>4</sub>, 0.5 M NiCl<sub>2</sub>, 0.01 M CuSO<sub>4</sub>, and 1 M H<sub>3</sub>BO<sub>3</sub>). The deposition process was performed at 27°C in a three-electrode cell with a Pt counter electrode and a SCE. PGP electrode with area of  $\sim 6 \text{ cm}^2$  was assembled as the working electrode. Through the potential scan from the open circuit potential (~0 V) in a negative direction, the onset of the Cu reduction current at approximately -0.1 V was followed by a reduction peak associated with the nucleation and growth of Cu metal film. As Cu<sup>2+</sup> has a limited mass transfer because of its small concentration, the deposition current varied tiny with potential until -0.75 V, at which point Ni<sup>2+</sup> began reduction. At more negative potential, Cu and Ni were co-deposited. The anodic peak about 0.5 V is attributed to a selective dissolution of Cu from the Cu-Ni layers in the deposit. The co-deposition of Cu-Ni layers and then the selective etching of Cu from the deposit were completed in the same plating solution on exchanging the applied potential at -0.85 V and +0.55 V, respectively. The Cu-Ni layers were first coated on PGP electrode at -0.85 V; total deposited charge was 20 Coulomb. Electrochemical etching of Cu from the Cu-Ni layer was executed on exchanging the potential to +0.55 V until a current density 20 µA/cm<sup>2</sup> to develop the Ni-nanotube layer. Chemical segregation within deposited Cu-Ni grains was observed by previous authors.<sup>1,2</sup> As a result, we have developed an efficient electrochemical technique to construct Ni-nanotube/PGP electrodes. The Ni-nanotube layer (excluding graphite or paper) loaded was on average 0.5 mg/cm<sup>2</sup> (XP105DR Mettler Toledo). MnO<sub>x</sub> nanofiber layers were loaded onto the Ni-nanotube/PGP substrate by electrodeposition at 0.45 V in a solution containing 0.3 M Mn(CH<sub>3</sub>COO)<sub>2</sub> (Sigma-Aldrich) and 0.1 M NH<sub>4</sub>CH<sub>3</sub>COO (Acros) at 27°C to assemble the nanoporous MO<sub>x</sub>/PGP electrodes with a Pt counter electrode and a SCE. The typical mass of the deposited oxide, measured with a microbalance (XP105DR Mettler Toledo, accuracy 0.1 mg), was ~12 mg. The mass of dead components (electrolyte, conductive paper, separator) was not considered to active materials (MnO<sub>x</sub> 2.0 mg/cm<sup>2</sup> and VO<sub>x</sub> 2.0 mg/cm<sup>2</sup>).

#### **Electrochemical measurements**

Electrochemical performances of VO<sub>x</sub>/PGP and MnO<sub>x</sub>/PGP electrodes were measured in KCl solution (1 M, 27 °C) using cyclic voltammetry (CV) with a Pt counter electrode and a SCE. A Pt wire immersed in PAL solution contained in a glass tube with porous Vycor tip (Bioanalytical Systems, MF-2042) was used as a quasi-reference electrode in LiClO<sub>4</sub>–acetamide or PAL electrolyte systems. And the performances of VO<sub>x</sub>/PGP and MnO<sub>x</sub>/PGP electrodes in PAL electrolyte were measured with a Pt counter electrode and a quasi-reference electrode. An electrochemical impedance spectroscopy (EIS) experiment was

studied using the frequency range from 0.1 Hz to 100 kHz with an amplitude of 5 mV. All electrochemical measurements were made with a potentiostat (AUTOLAB).

#### **Calculation method**

 $C_{sp}$  of cyclic voltammetry (CV) and galvanostatic charge-discharge (GCD) cycles in a three electrode system are calculated as follows,

$$C_{sp} = Q_{\rm m} \,/\, \Delta V \tag{1}$$

$$C_{sp} = I \Delta t / \Delta V w \qquad (2)$$

in which  $Q_m$  denotes the specific voltammetric charge ((based on mass of VO<sub>x</sub> or MnO<sub>x</sub>) integrated from CV,  $\Delta V$  denotes the scanning range, *I* is applied current density (1–50 A/g), *w* is VO<sub>x</sub> or MnO<sub>x</sub> mass and  $\Delta t$  is duration of discharge cycling. With chargedischarge curves based on two electrode systems,  $C_{asy}$  is specific capacitance of an asymmetric supercapacitor, derived from GCD acquired by the equation  $C_{asy} = I \Delta t / \Delta V$ *W*, in which  $W (W = w^+ + w^-)$  means the total active material masses on both positive and negative electrodes. The energy density (*E*) and power density (*P*) are calculated from the GCD curves according to eqs 3 and 4,<sup>3-5</sup>

$$E = 1/2 \ C_{asy} \,\Delta V^2 \tag{3}$$

$$P = E / \Delta t \tag{4}$$

in which  $\Delta V$  is cell voltage (*i.e.* 4.2 V) and  $\Delta t$  is discharge time.



Figure S1. (a) Effect of addition of PAL gel to ink on the local sheet resistivity. The error ranges of all bars presented here are  $\pm 10\%$ . (b) Shear rheometry data for the acetamide-LiClO<sub>4</sub> and PAL electrolyte.



Figure S2. BJH pore size distributions of (a)  $VO_x$  nanoporous and (b)  $MnO_x$  nanofibers. Inset are N<sub>2</sub> adsorption/desorption isotherms of (a)  $VO_x$  nanoporous and (b)  $MnO_x$  nanofibers.



Figure S3. XRD patterns of (a)  $VO_x$  nanoporous and (b)  $MnO_x$  nanofibers.



Figure S4. Core-level XPS spectrum of V  $2p_{3/2}$  for a VO<sub>x</sub> film.



Figure S5. CVs of  $VO_x/PGP$  and bare PGP electrodes in PLA electrolyte at 5 mV/s.



Figure S6.  $C_{sp}$  retentions of the VO<sub>x</sub>/PGP electrode in PAL gel electrolyte and in KCl

solution as a function of scan rate.



Figure S7.  $C_{sp}$  retentions of the MnO<sub>x</sub>/PGP electrode in PAL gel electrolyte and in KCl

solution as a function of scan rate.



**Figure S8.** Cycling performance of VO<sub>x</sub>/PGP and MnO<sub>x</sub>/PGP electrodes in PAL gel and KCl

solution.



Figure S9. CV curves of the potential limits for  $VO_x/PGP$  and  $MnO_x/PGP$  in PAL electrolytes at 5 mV/s.



Figure S10. Schematic illustration of the assembled HVWASC devices.



Figure S11. GCD curves of the HVWASC device under various current densities (1–50 A/g)



Figure S12. Nyquist plot for HVWASC device using a sinusoidal signal of 5 mV. (Z' is real

impedance. Z" is imaginary impedance.)

### References

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